

# Special Topics on Basic EECS I Design Technology Co-Optimization

## Lecture 22

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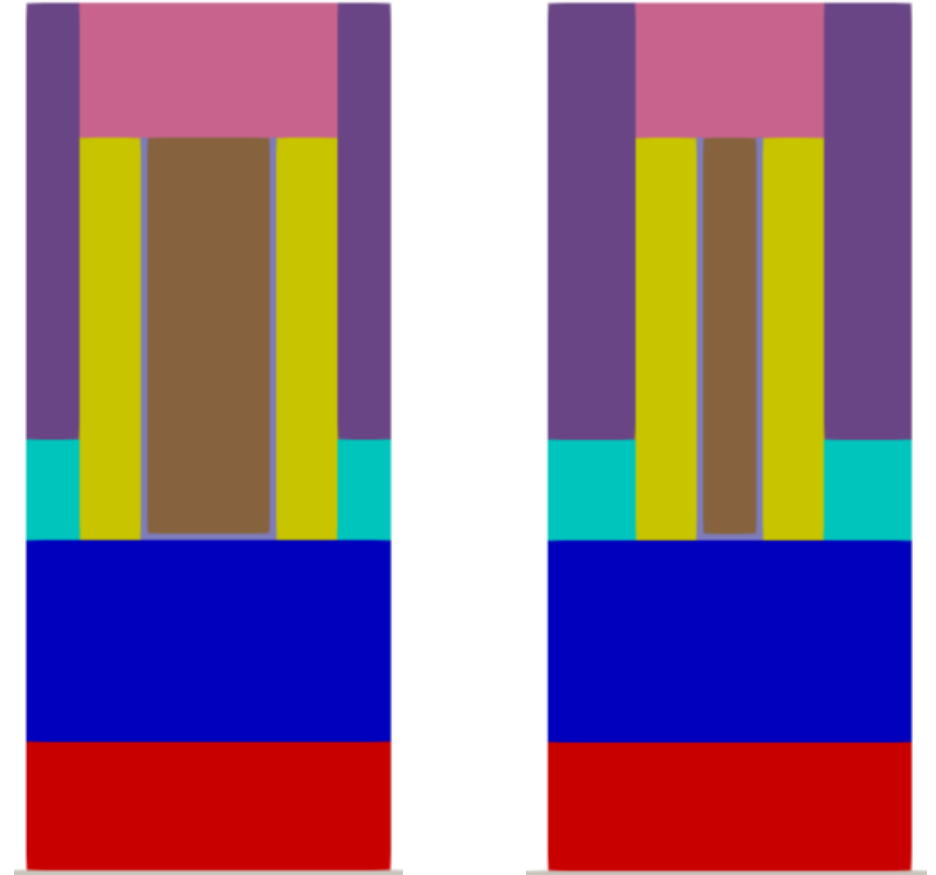
# L22

$$\mathbf{CPP} = L_G + 2L_{spacer} + L_{SD}$$

- When the CPP is fixed, we must decompose it into three parameters.
  - If  $L_G$  decreases, the channel conductance improves. But, the short channel effect becomes significant.
  - If  $L_{spacer}$  decreases, again, the short channel effect.
  - If  $L_{SD}$  decreases, the source/drain resistance increases.
  - Note: Our  $L_G$  includes the high-k thickness (twice).
- Other geometric parameters are fixed.
  - No calibration for material parameters
- Perfect contact alignment

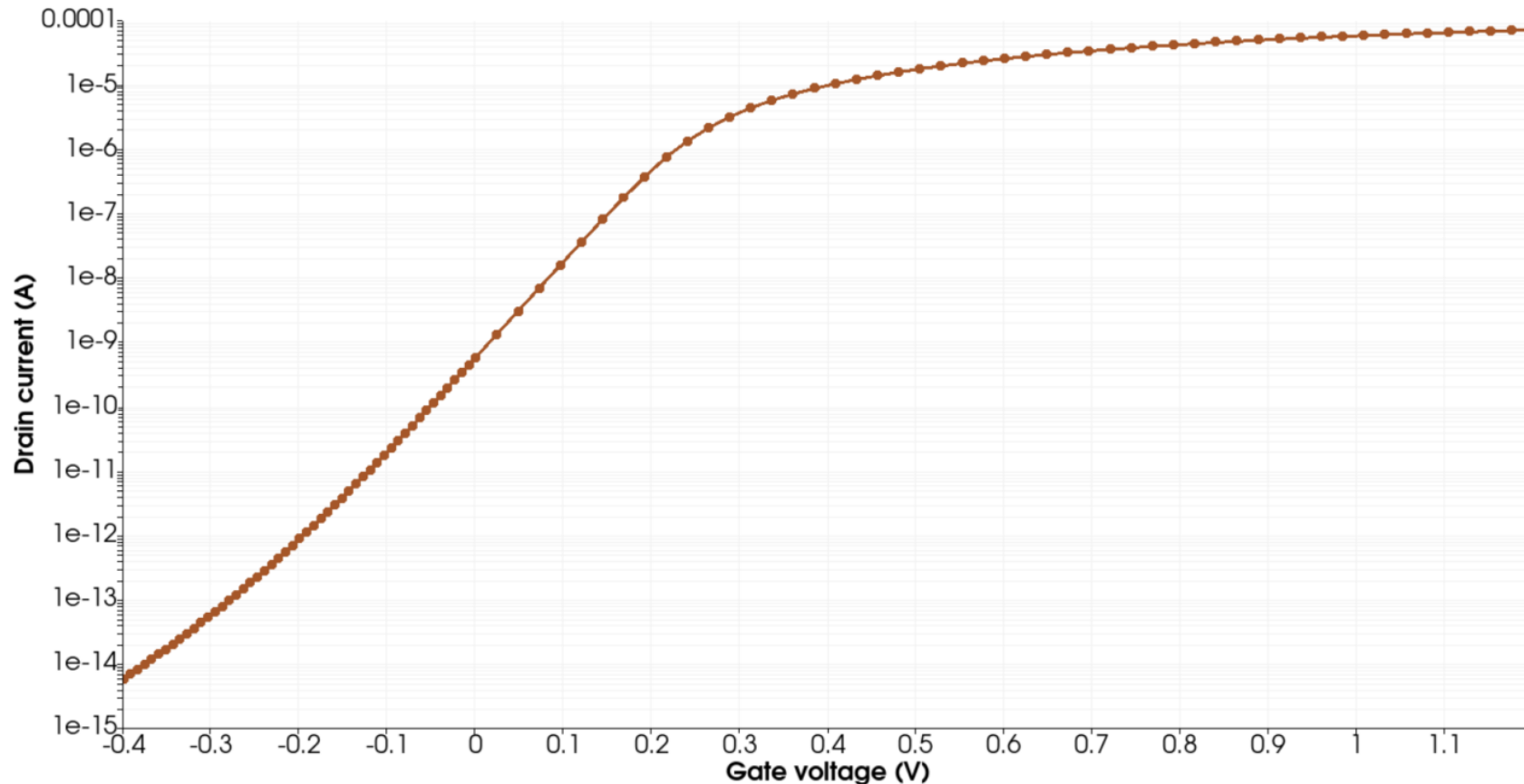
# A scenario of $L_{spacer} = 9$ nm

- It means  $L_G + L_{SD} = 36$  nm.
  - Measure  $I_{ON}$  with  $I_{OFF} = 1$  nA.
  - How can we find it efficiently?
  - Run a simulation with a wider voltage range. Then, just shift it.
  - List of  $L_G$  values: 20 nm (Baseline), 18 nm, 16 nm, 14 nm, 12 nm, and 10 nm



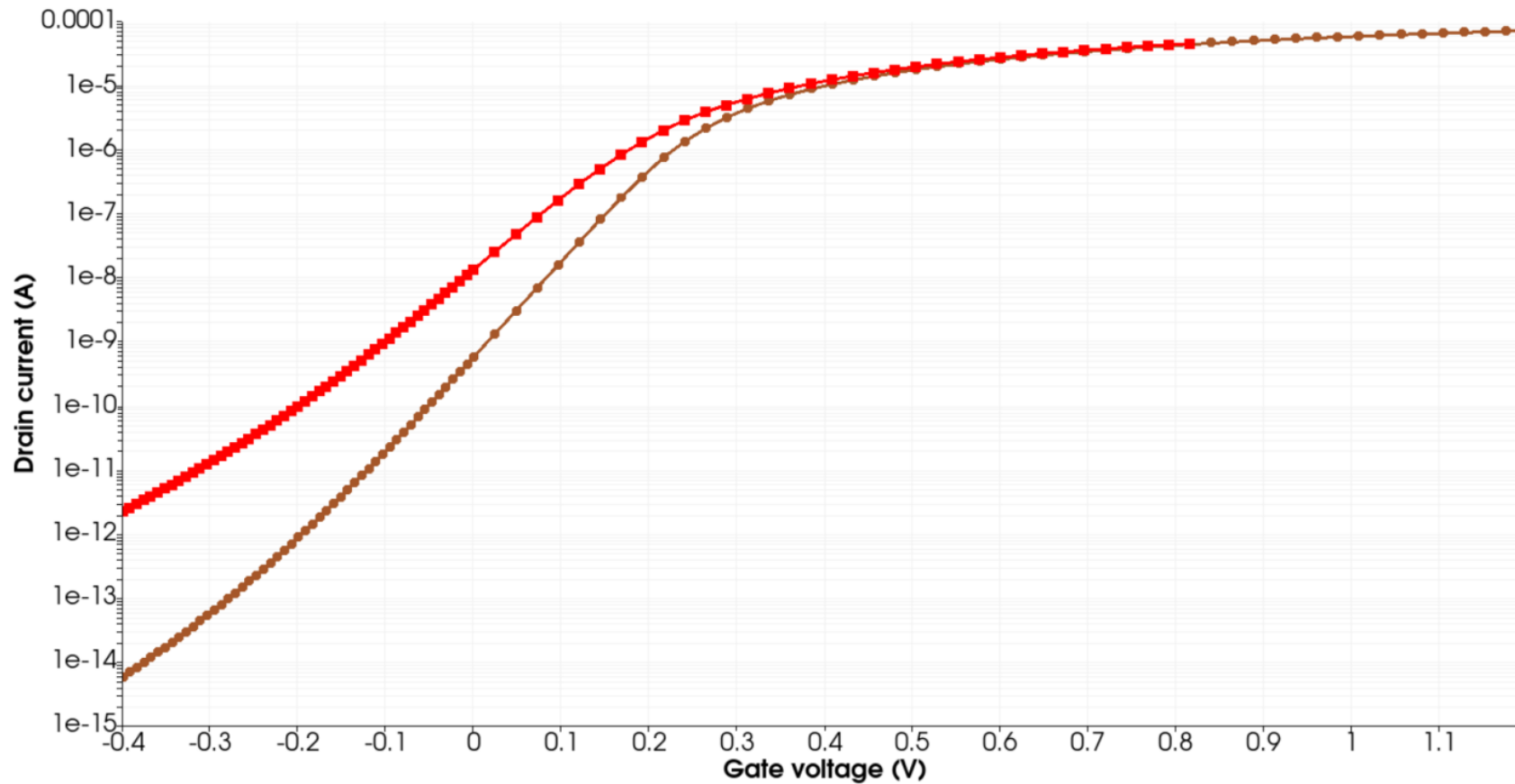
# Data for $L_G = 20$ nm

- Workfunction of 4.4 eV
  - After shifting  $\sim 16$  mV,  $I_{ON}$  is  $\sim 35.2$   $\mu$ A. (Or, 496  $\mu$ A/ $\mu$ m with effective width)



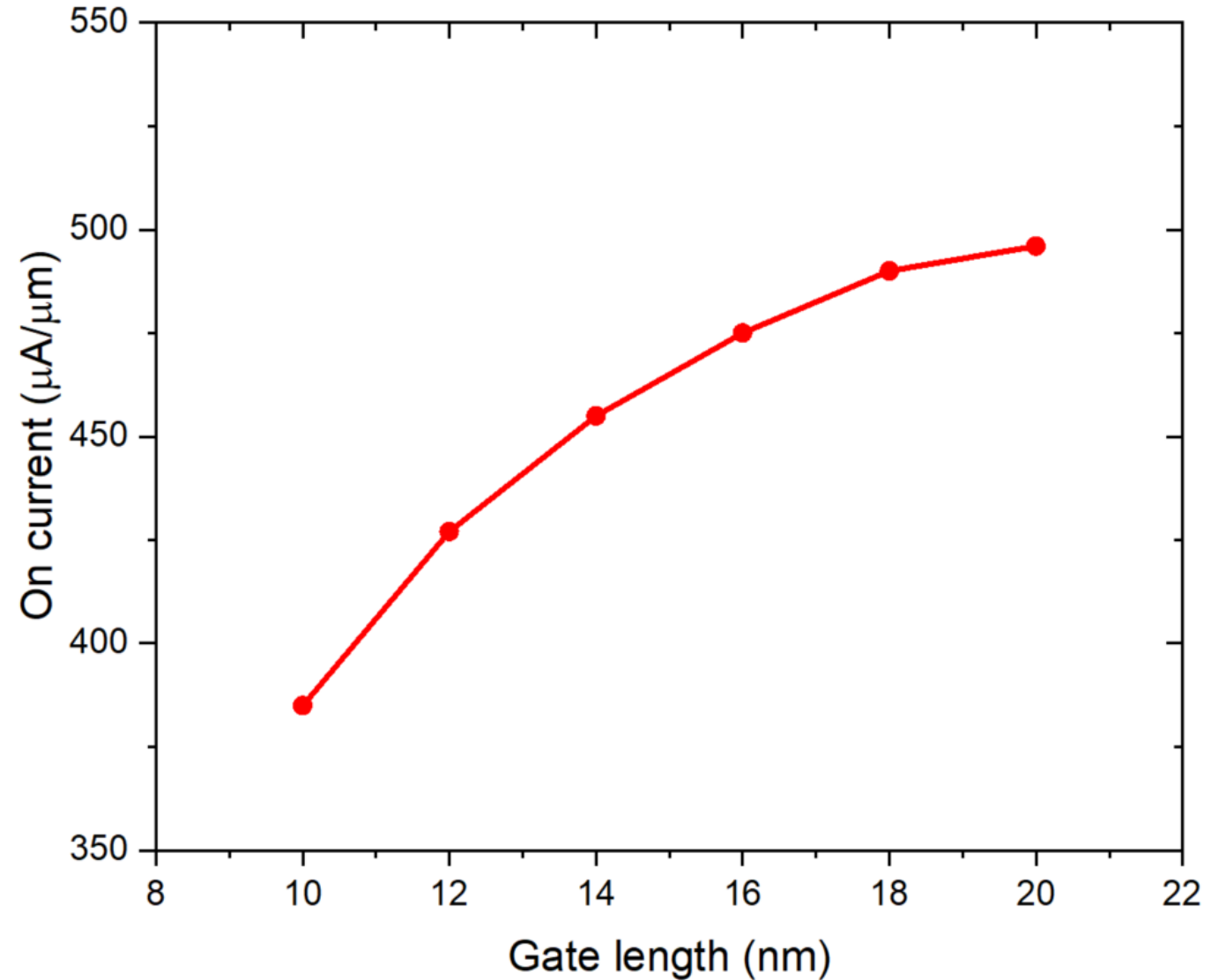
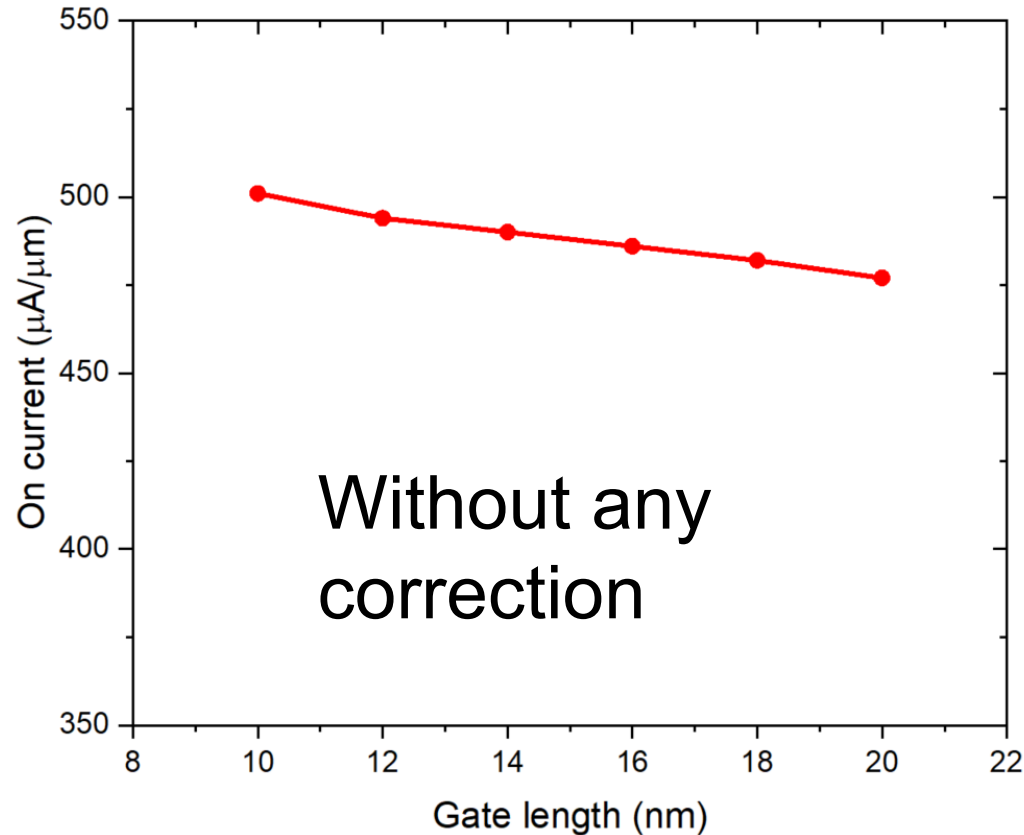
# Data for $L_G = 10$ nm

- Workfunction of 4.4 eV
  - Now,  $I_{ON}$  is  $\sim 27.3$   $\mu\text{A}$ . (Or, 385  $\mu\text{A}/\mu\text{m}$  with effective width)
  - 22 % reduction due to the short channel effect



# $I_{ON}$ (@ iso- $I_{OFF}$ ) as a function of $L_G$

- $L_G$  scaling degrades  $I_{ON}$ .
  - It does not follow  $\propto \frac{1}{L_G}$ .



# Thank you!